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Date

Ayesha S. Wilks

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Vishnu K. Agarwal Attorney Docket No.: 501082.06 (98-0616.05)  
Serial No. : 09/652,842 Group Art Unit : 2825  
Filed : August 31, 2000 Examiner : Belur V. Keshavan  
Title : DEVICE AND METHOD FOR PROTECTING AGAINST OXIDATION OF A  
CONDUCTIVE LAYER IN SAID DEVICE

Box Non-Fee Amendment  
Commissioner of Patents  
Washington, DC 20231

## AMENDMENT

Sir:

Please amend the above-captioned patent application as follows:

**In the Specification:**

Please replace the paragraph beginning at page 8, line 4, with the following rewritten paragraph:

--Still other gases include diborane ( $B_2H_6$ ); phosphine ( $PH_3$ ); and carbon-silicon compounds such as methylsilane ( $CH_3SiH_3$ ) and hexamethyldisilane ( $CH_3)_3Si-Si(CH_3)_3$ ; and hexamethyldisilazane (HMDS). Additional alternate embodiments of the current invention use hydrazine ( $N_2H_4$ ), monomethylhydrazine, carbon tetrafluoride ( $CF_4$ ),  $CHF_3$ ,  $HCl$ , and boron trichloride ( $BCl_3$ ), which are also useful in passivating dielectrics, as addressed in copending application 09/114,847, now issued as U.S. Patent No. 6,201,276 B1. Also included are mixtures of any of the gases or types of gases described above. Exemplary non-plasma process parameters using these other gases include a flow rate of about 2 sccm to about 400 sccm for

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